

SECOND SEMESTER 2018 - 2019

Course Handout Part II

07.01.2019

In addition to Part I (general Handout for all courses appended to the Time Table), this portion gives further specific details regarding the course.

Course No. : PHY F379

Course Title : Thin film technology

Instructors : **Dr. V. Satya Narayan Murthy** & Prof. Harihara

Venkataraman

Course Description: This course gives an overview of thin film technology - Basics of vacuum science and technology, Thin film deposition techniques; Kinetics and diffusion mechanisms, Surface nucleation and film growth, Structure and morphology of thin films, Electrical and magnetic properties, Special topics on thin film application.

Scope & Objective:

- ➤ The course introduces the concepts in vacuum deposition techniques, nucleation and growth of thin films.
- > Techniques to characterize the thin films and some of the physical properties of films and their applications.

Text Book: No single textbook exists. Lecture notes will be distributed.

Reference Books:

- ➤ Materials Science of Thin Films Milton Ohring, 2nd Edition (Elsevier)
- A User's Guide to Vacuum Technology J.F. O' Hanlan
- > Thin film deposition principles and practice Smith Donald
- > Thin Film Phenomena Kasturi L Chopra (McGraw Hill)

Course Plan:

| Lectur e No. | Learning Objectives | Topics to be covered | Reference (Chap/Sec) |
|-----------------|---------------------|---|---------------------------------|
| 1 - 6 | Vacuum technology | Mean free path, gas flow regimes, conductance, pumping speed, vacuum levels, working principles of different vacuum pumps, vacuum gauges, vacuum leak detection, vacuum seals | notes + relevant portions |



| 7 - 10 | Thin film deposition | Differences between CVD and PVD, different PVD techniques – thermal and electron beam evaporation, sputtering, PLD, MBE, etc., evaporation rate, evaporation of multielement materials and alloys | reference books |
|---------|-----------------------|---|--------------------|
| 11 - 14 | Film thickness | Thickness measurement techniques, | |
| | uniformity and purity | deposition geometry, thickness uniformity | |
| 15 - 20 | Nucleation and | Thermodynamic aspects of | |
| | growth of thin film | nucleation and growth – capillarity | |
| | | theory of heterogeneous nucleation, | |
| | | atomistic theory, growth modes | |
| 21 - 28 | Characterization | Structural techniques (XRD), imaging | |
| | techniques | techniques (SEM / TEM), optical | |
| | | techniques, chemical techniques | |
| 29 - 34 | Properties of thin | Electrical, dielectric, ferroelectric and | |
| | films | magnetic properties | |
| 35 - 40 | Applications | Sensors, solar cells, giant | |
| | | magnetoresistance, ferroelectronic | |
| | | effect, multiferroics | |

Evaluation Scheme:

| EC No | Evaluation Scheme | Duratio n | Weightag e (%) | Date & Time | Nature of Componen t |
|----------|----------------------|--------------|-------------------|-----------------------|----------------------------|
| 1. | Midsem | 90 mins | 35 | 12/3 1.30 -3.00 PM | Closed |
| | Examination | | | 1130 3100 1111 | Book |
| 2. | Quiz/Seminar | | 20 | | Open Book |
| 3. | Comprehensive | 3 hrs | 45 | 04/05 FN | Open Book |
| | Examination | | | | |

Notices: Notices for the course will be displayed on **Physics** notice board.

Make-up Policy: Make up will be given strictly to **genuine cases only** i.e. **(i)** <u>Sickness leading to hospitalization</u>, **(ii)** <u>Out of station with prior intimation & permission</u>. No make-up for Quiz / Seminar components.

Academic Honesty and Integrity Policy: Academic honesty and integrity are to be maintained by all the students throughout the semester and no type of academic dishonesty is acceptable.



